

ABSTRACT OF THE DISCLOSURE

1 In an apparatus for etching a glass substrate according to the present invention,
2 impurities that are attached to the surface of a glass substrate, which are formed by
3 assembling a color filter substrate and a TFT substrate provided in the etching bath filled with
4 etchant, are removed by using ultrasonic oscillation generated from an ultrasonic oscillator,
5 by which a glass substrate having uniform thickness and surface is obtained.